

**SESSION 22 – TAPA I**  
**Nonvolatile Memories**

Friday, June 18, 3:40 p.m.

Chairperson: O. Jungroth, Intel Corporation  
N. Lu, Etron Technology, Inc.

**22.1 - 3:40 p.m.**

**A 100MHz Ladder FeRAM Design with Capacitance-Coupled-Bitline (CCB) Cell**, D. Takashima, Y. Nagadomi, T. Ozaki, Toshiba Corp, Japan

This paper proposes a new ladder FeRAM architecture with CCB cell for high-end embedded application. This configuration realizes small  $0.35\mu\text{m}^2$  cell using highly reliable large ferroelectric capacitor of  $0.145\mu\text{m}^2$  and highly compatible process with logic-LSI. The proposed ladder FeRAM with a new early plateline pull-down read scheme also achieves fast random read/write of 10ns cycle and 8ns access at 150C. A 64Kb test chip using 128Mb chain FeRAM process is designed to verify these performances.

**22.2 - 4:05 p.m.**

**A Low Store Energy, Low VDDmin, Nonvolatile 8T2R SRAM with 3D Stacked RRAM Devices for Low Power Mobile Applications**, P.-F. Chiu, M.-F. Chang, S.-S. Sheu\*, \*K.-F. Lin, P.-C. Chiang\*, C.-W. Wu, W.-P. Lin\*, C.-H. Lin\*, C.-C. Hsu, F.T. Chen\*, K.-L. Su\*, M.-J. Kao\*, M.-J. Tsai\*, National Tsing Hua University, Taiwan, \*EOL, ITRI, Taiwan

This work demonstrates the first fabricated macro-level RRAM-based nonvolatile SRAM that use a new 8T2R (Rnv8T) cell to achieve fast NVM storage and low VDDmin read/write operations. The Rnv8T cell uses two RRAM devices, 3D stacked over the 8T, to achieve low store energy with a compact cell area. A 2T RRAM-switch provides write-assist functions. The fabricated 16Kb Rnv8T macro achieves the lowest store energy and R/W VDDmin (0.45V) than other nvSRAM and "SRAM+NVM" solutions.

**22.3 - 4:30 p.m.**

**OxID: On-Chip One-Time Random ID Generation using Oxide Breakdown**, N. Liu, S. Hanson, D. Sylvester, D. Blaauw, University of Michigan, USA

A new chip ID generation method is presented that leverages the random and permanent characteristics of oxide breakdown. A 128b ID array is implemented in 65nm CMOS and two algorithms for stressing the oxides are presented, showing a near-ideal Hamming distance of 63.92 in silicon measurements and consistent IDs across voltage and temperature.

**22.4 - 4:55 p.m.**

**A 60% Higher Write Speed, 4.2Gbps, 24-Channel 3D-Solid State Drive (SSD) with NAND Flash Channel Number Detector and Intelligent Program-Voltage Booster**, T. Hatanaka, K. Ishida, T. Yasufuku, S. Miyamoto\*, H. Nakai\*, M. Takamiya, T. Sakurai, K. Takeuchi, University of Tokyo, \*Toshiba Corporation, Japan

The fastest ever 4.2Gbps 3D-SSD with the NAND flash channel number detector and the intelligent boosting scheme is proposed. By dynamically optimizing the switching clock of the booster, the proposed 3D-SSD achieves both the fastest write and the lowest energy consumption. In the sequential write with a large data size, the SSD write speed increases by 60%. In the random write with a small data size, the energy consumption of the booster decreases by 32%.